

PATENT  
2185-0343P

## IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Yasunori UETANI et al. Conf.: 8929

Appl. No.: 09/323,230 Group: 1752

Filed: June 1, 1999 Examiner: CHU, JOHN SY

For: A POSITIVE RESIST COMPOSITION

REPLY UNDER 37 C.F.R. § 1.116Assistant Commissioner for Patents  
Washington, DC 20231

May 13, 2002

Sir:

In response to the Office Action of November 23, 2001, the period for response having been extended two months, the following amendments and remarks are submitted in connection with the above-identified application.

AMENDMENTSIN THE CLAIMS:

*Do not  
alter  
file 5/2002*

Please amend the claims as follows.

1. (Amended) An article comprising a substrate comprising a silicon wafer and a positive resist composition comprising a novolac resin; an o-quinonediazide sulfonic acid ester of a compound having a phenolic hydroxyl group; and a thioxanthone compound represented by the following formula(I):

05/23/2002 RWIMBUSH 00000001-022448 09323230

01 FC:117 920.00 CH

Adjustment date: 12/13/2002 EERNRAY1  
05/23/2002 RWIMBUSH 00000001 022448 09323230

01 FC:1N 920.00 CR